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<table style="width: 100%; border: none;"> <tr> <td style="width: 50%; vertical-align: top; border: none; padding: 5px;"> (21) International Application Number: PCT/US96/15368 (22) International Filing Date: 25 September 1996 (25.09.96) (30) Priority Data: 08/538,475 3 October 1995 (03.10.95) US (71) Applicant: ADVANCED REFRACTORY TECHNOLOGIES, INC. [US/US]; 699 Hertel Avenue, Buffalo, NY 14207 (US). (72) Inventors: GOEL, Arvind; 156 Highgate Avenue, Buffalo, NY 14214 (US). BRAY, Donald, J.; 257 Sausalito Drive, East Amherst, NY 14051 (US). MARTIN, Steven, C.; 123 E. Pinelake Drive, Williamsville, NY 14221 (US). BLAKELY, Keith, A.; 63 Morris Avenue, Buffalo, NY 14214 (US). (74) Agents: WEYAND, Karla, M. et al.; Nixon, Hargrave, Devans & Doyle L.L.P., Clinton Square, P.O. Box 1051, Rochester, NY 14603 (US). </td> <td style="width: 50%; vertical-align: top; border: none; padding: 5px;"> (81) Designated States: AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CU, CZ, DE, DK, EE, ES, FI, GB, GE, HU, IL, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, TJ, TM, TR, TT, UA, UG, UZ, VN, ARIPO patent (KE, LS, MW, SD, SZ, UG), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG). Published <i>With international search report. Before the expiration of the time limit for amending the claims and to be republished in the event of the receipt of amendments.</i> </td> </tr> </table>			(21) International Application Number: PCT/US96/15368 (22) International Filing Date: 25 September 1996 (25.09.96) (30) Priority Data: 08/538,475 3 October 1995 (03.10.95) US (71) Applicant: ADVANCED REFRACTORY TECHNOLOGIES, INC. [US/US]; 699 Hertel Avenue, Buffalo, NY 14207 (US). (72) Inventors: GOEL, Arvind; 156 Highgate Avenue, Buffalo, NY 14214 (US). BRAY, Donald, J.; 257 Sausalito Drive, East Amherst, NY 14051 (US). MARTIN, Steven, C.; 123 E. Pinelake Drive, Williamsville, NY 14221 (US). BLAKELY, Keith, A.; 63 Morris Avenue, Buffalo, NY 14214 (US). (74) Agents: WEYAND, Karla, M. et al.; Nixon, Hargrave, Devans & Doyle L.L.P., Clinton Square, P.O. Box 1051, Rochester, NY 14603 (US).	(81) Designated States: AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CU, CZ, DE, DK, EE, ES, FI, GB, GE, HU, IL, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, TJ, TM, TR, TT, UA, UG, UZ, VN, ARIPO patent (KE, LS, MW, SD, SZ, UG), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG). Published <i>With international search report. Before the expiration of the time limit for amending the claims and to be republished in the event of the receipt of amendments.</i>
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(54) Title: CAPACITIVE THIN FILMS USING DIAMOND-LIKE NANOCOMPOSITE MATERIALS				
(57) Abstract A method of making capacitors (25) comprising, providing as the dielectric (27) and/or conductive layers (26), a material made from a diamond-like nanocomposite solid-state material having interpenetrating atomic scale networks of carbon in a diamond-like carbon network stabilized by hydrogen, a glass-like silicon network stabilized by oxygen, and optionally at least one additional network of dopant elements or dopant compounds having elements from Groups 1-7b and 8 of the periodic table.				